

# ABSTRACT OF THE DISCLOSURE

The invention provides new light absorbing crosslinking compositions suitable for use as an antireflective composition, particularly for deep UV applications: The antireflective compositions of the invention comprise a photoacid generator that is activated during exposure of an overcoated photoresist. Antireflective compositions of the invention can significantly reduce undesired footing of an overcoated resist relief image.

0904587 071441  
FOI 2012 0540660